S/N Unknown

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Stephen Y. Chou

Examiner: Unknown

Serial No.:

Unknown

Group Art Unit: Unknown

Filed:

Herewith

Docket: 600.426US2

Title:

IMPROVED RELEASE SURFACES, PARTICULARLY FOR USE IN

NANOIMPRINT LITHOGRAPHY

PRELIMINARY AMENDMENT

Commissioner for Patents Washington, D.C. 20231

Prior to examination, please amend the above-identified divisional application as follows:

IN THE SPECIFICATION

On page 1, line 7, please add the following:

RELATED APPLICATIONS

This application is a divisional of U.S. Patent Application Serial No. 09/107,006, filed June 30, 1998, which claims priority to U.S. Patent No. 6,772,905, issued June 30, 1998.

IN THE CLAIMS

Please substitute the claim set in the appendix entitled Clean Version of Pending Claims for the previously pending claim set. The substitute claim set is intended to reflect cancellation of claims 2-41, and addition of new claims 42-59. The specific amendments to individual claims are detailed in the following marked up set of claims.

- 42. The method of claim 1 wherein the film comprises a material that passes from a flowing state to a non-flowing state during the molding process.
- 43. The method of claim 42 wherein the film comprises a thermoplastic, hardenable or curable material.

- 44. The method of claim 42 wherein the material passes from a flowing state to a non-flowing state upon change of temperature, pressure, polymerization, irradiation or charging.
- 45. The method of claim 1 wherein the film comprises a film layer selected from the group consisting of: polymer film, latex film, viscous polymer coating, composite coating, fusible powder coating, adherent powder coating or fusible powder coating.
- 46. The method of claim 1 wherein the film comprises a moldable polymer.
- 47. The method of claim 1 wherein the film comprises a moldable polymer selected from the group consisting of: acrylates, methacrylates, polycarbonates, polyvinyl resins, polyimides, polyurethanes, polysiloxanes, polyesters and polyethers.
- 48. The method of claim 1 wherein the film comprises metal oxides, metal halides, semimetal oxides or semimetal halides.
- 49. The method of claim 48 wherein the film is a sol.
- 50. The method of claim 1 wherein the film comprises microfibers.
- 51. The method of claim 1 wherein the film comprises a multilayer of films.
- 52. The method of claim 1 wherein the substrate comprises a semiconductor, insulator or metal.
- 53. The method of claim 1 wherein the substrate comprises a single crystal material.
- 54. The method of claim 1 where in the substrate comprises an amorphous material.

- The method of claim 1 where the substrate comprises a composite material. 55.
- The method of claim 1 where the substrate comprises a multilayer substrate. <u>56.</u>
- The method of claim 1 wherein the pattern in the mask material is transferred to one layer 57. of a multilayer film.
- The method of claim 1 wherein the pattern in the mask material is more than one layer of 58. a multilayer film.
- The method of claim 1 wherein the pattern transferred to one layer of a multilayer film is 59. used as a mask to pattern the underlying layers in the multilayer film.

CONCLUSION

Claims 2-41 have been cancelled without prejudice, and new claims 42-59 have been added. Claims 1 and 42-59 are pending in this application.

The Examiner is invited to call Applicant's attorney (612-359-3261) if there are any questions concerning this application.

Respectfully submitted,

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This paper or fee is being deposited on the date indicated above with the United States Postal Service pursuant to 37 CFR 1.10, and is addressed to The Commissioner for Patents, Box Patent Application, Washington, D.C 20231.

Clean Version of Pending Claims

IMPROVED RELEASE SURFACES, PARTICULARLY FOR USE IN NANOIMPRINT LITHOGRAPHY

Applicant: Stephen Y. Chou Serial No.:

- 42. The method of claim 1 wherein the film comprises a material that passes from a flowing state to a non-flowing state during the molding process.
- 43. The method of claim 42 wherein the film comprises a thermoplastic, hardenable or curable material.
- 44. The method of claim 42 wherein the material passes from a flowing state to a non-flowing state upon change of temperature, pressure, polymerization, irradiation or charging.
- 45. The method of claim 1 wherein the film comprises a film layer selected from the group consisting of: polymer film, latex film, viscous polymer coating, composite coating, fusible powder coating, adherent powder coating or fusible powder coating.
- 46. The method of claim 1 wherein the film comprises a moldable polymer.
- 47. The method of claim 1 wherein the film comprises a moldable polymer selected from the group consisting of: acrylates, methacrylates, polycarbonates, polyvinyl resins, polyimides, polyurethanes, polysiloxanes, polyesters and polyethers.
- 48. The method of claim 1 wherein the film comprises metal oxides, metal halides, semimetal oxides or semimetal halides.

- 49. The method of claim 48 wherein the film is a sol.
- 50. The method of claim 1 wherein the film comprises microfibers.
- 51. The method of claim 1 wherein the film comprises a multilayer of films.
- 52. The method of claim 1 wherein the substrate comprises a semiconductor, insulator or metal.
- 53. The method of claim 1 wherein the substrate comprises a single crystal material.
- 54. The method of claim 1 where in the substrate comprises an amorphous material.
- 55. The method of claim 1 where the substrate comprises a composite material.
- 56. The method of claim 1 where the substrate comprises a multilayer substrate.
- 57. The method of claim 1 wherein the pattern in the mask material is transferred to one layer of a multilayer film.
- 58. The method of claim 1 wherein the pattern in the mask material is more than one layer of a multilayer film.
- 59. The method of claim 1 wherein the pattern transferred to one layer of a multilayer film is used as a mask to pattern the underlying layers in the multilayer film.

Clean Version of Specification Paragraphs

 ${\small \mbox{IMPROVED RELEASE SURFACES, PARTICULARLY FOR USE IN NANOIMPRINT } \\ {\small \mbox{LITHOGRAPHY}}$

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RELATED APPLICATIONS

This application is a divisional of U.S. Patent Application Serial No. 09/107,006, filed June 30, 1998, which claims priority to U.S. Patent No. 6,772,905, issued June 30, 1998.